

	Hits	Search Text	DBs
1	8	((immers\$6 or liquid) near8 (lithograph\$6 or photolithograph\$6)) and ((photoresist or resist or photosensitive) same (substrate or wafer or device or platen or template) same (protective or top\$6coat\$4 or upper or hard\$5mask\$4)) and (expos\$6 or illuminat\$4 or irradiat\$4) and solubili\$8 and ((acid or photo\$4acid or (therm\$5 near6 acid)) near15 (generat\$4 or liberat\$5)) and (BARC or (bottom near9 ARC) or (ARC near14 under\$3layer) or (bottom near13 anti\$5reflect\$6))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
2	11	((immers\$6 or liquid) near8 (lithograph\$6 or photolithograph\$6)) and ((photoresist or resist or photosensitive) same (substrate or wafer or device or platen or template)) and ((resist or photoresist or photosensitive or photo\$5cur\$5 or (radiation near9 sensitive)) same (protective or top\$6coat\$4 or upper or hard\$5mask\$4)) and (expos\$6 or illuminat\$4 or irradiat\$4) and solubili\$8 and ((acid or photo\$4acid or (therm\$5 near6 acid)) near15 (generat\$4 or liberat\$5)) and (BARC or (bottom near9 ARC) or (ARC near14 under\$3layer) or (bottom near13 anti\$5reflect\$6))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
3	63	((immers\$6 or liquid) near22 (lithograph\$6 or photolithograph\$6)) and ((photoresist or resist or photosensitive) same (substrate or wafer or device or platen or template)) and ((resist or photoresist or photosensitive or photo\$5cur\$5 or (radiation near9 sensitive)) same (protective or top\$6coat\$4 or upper or hard\$5mask\$4 or over\$3coat\$4 or top\$4layer)) and (expos\$6 or illuminat\$4 or irradiat\$4) and ((acid or photo\$4acid or (therm\$5 near6 acid)) near15 (generat\$4 or liberat\$5)) and (BARC or (bottom near9 ARC) or (ARC near14 under\$3layer) or (bottom near13 anti\$5reflect\$6) or anti\$8reflect\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
4	52	S3 NOT S2	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
5	58	((immers\$6 or liquid) near12 (lithograph\$6 or photolithograph\$6)) and ((photoresist or resist or photosensitive) same (substrate or wafer or device or platen or template)) and ((resist or photoresist or photosensitive or photo\$5cur\$5 or (radiation near9 sensitive)) same (protective or top\$6coat\$4 or upper or hard\$5mask\$4 or over\$3coat\$4 or top\$4layer)) and (expos\$6 or illuminat\$4 or irradiat\$4) and ((acid or photo\$4acid or (therm\$5 near6 acid)) near15 (generat\$4 or liberat\$5)) and (BARC or (bottom near9 ARC) or (ARC near14 under\$3layer) or (bottom near13 anti\$5reflect\$6) or anti\$8reflect\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
6	47	S5 NOT S2	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
12	18	((immersion near14 lithography) or ((liquid or fluid) near9 immersion near14 (system or apparatus or method))) and ((photoresist or resist or photosensitive) same (substrate or wafer or device or platen or template)) and ((resist or photoresist or photosensitive or photo\$5cur\$5 or (radiation near9 sensitive)) same (protective or top\$6coat\$4 or upper\$8layer or hard\$5mask\$4 or over\$3coat\$4 or top\$4layer)) and (expos\$6 or illuminat\$4 or irradiat\$4) and ((acid or photo\$4acid or (therm\$5 near6 acid)) near15 (generat\$4 or liberat\$5)) and (BARC or (bottom near9 ARC) or (ARC near14 under\$3layer) or (bottom near13 anti\$5reflect\$6) or anti\$8reflect\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
13	18	((immersion near14 lithography) or ((liquid or fluid) near9 immersion near14 (system or apparatus or method))) and ((resist or photoresist or photosensitive or photo\$5cur\$5 or (radiation near9 sensitive)) same (protective or top\$6coat\$4 or upper\$8layer or hard\$5mask\$4 or over\$3coat\$4 or top\$4layer)) and (expos\$6 or illuminat\$4 or irradiat\$4) and ((acid or photo\$4acid or (therm\$5 near6 acid)) near15 (generat\$4 or liberat\$5)) and (BARC or (bottom near9 ARC) or (ARC near14 under\$3layer) or (bottom near13 anti\$5reflect\$6) or anti\$8reflect\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
14	20	((immersion near14 (lithograph\$8 or photolitho\$8)) or ((liquid or fluid) near9 immersion near14 (system or apparatus or method))) and ((resist or photoresist or photosensitive or photo\$5cur\$5 or (radiation near9 sensitive)) same (protective or top\$6coat\$4 or upper\$8layer or hard\$5mask\$4 or over\$3coat\$4 or top\$4layer)) and (expos\$6 or illuminat\$4 or irradiat\$4) and ((acid or photo\$4acid or (therm\$5 near6 acid)) near15 (generat\$4 or liberat\$5)) and (BARC or (bottom near9 ARC) or (ARC near14 under\$3layer) or (bottom near13 anti\$5reflect\$6) or anti\$8reflect\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
15	25	((immersion near14 (lithograph\$8 or photolitho\$8)) or ((liquid or fluid) near9 immersion near14 (system or apparatus or method))) and ((resist or photoresist or photosensitive or photo\$5cur\$5 or (radiation near9 sensitive)) same ((double near9 \$5resist) or (dual\$5 near5 resist\$5 near5 layer) or bi\$4layer or protective or top\$6coat\$4 or upper\$8layer or hard\$5mask\$4 or over\$3coat\$4 or top\$4layer)) and (expos\$6 or illuminat\$4 or irradiat\$4) and ((acid or photo\$4acid or (therm\$5 near6 acid)) near15 (generat\$4 or liberat\$5)) and (BARC or (bottom near9 ARC) or (ARC near14 under\$3layer) or (bottom near13 anti\$5reflect\$6) or anti\$8reflect\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
16	27	((immersion near14 (lithograph\$8 or photolitho\$8)) or ((liquid or fluid) near18 immersion near19 (system or apparatus or method))) and ((resist or photoresist or photosensitive or photo\$5cur\$5 or (radiation near9 sensitive)) same ((multi\$3 near9 resist) or (multiple near9 layer) or (double near9 \$5resist) or (dual\$5 near5 resist\$5 near5 layer) or bi\$4layer or protective or top\$6coat\$4 or upper\$8layer or hard\$5mask\$4 or over\$3coat\$4 or top\$4layer)) and (expos\$6 or illuminat\$4 or irradiat\$4) and ((acid or photo\$4acid or (therm\$5 near6 acid)) near15 (generat\$4 or liberat\$5)) and (BARC or (bottom near9 ARC) or (ARC near14 under\$3layer) or (bottom near13 anti\$5reflect\$6) or anti\$8reflect\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
17	37	((immersion near14 (lithograph\$8 or photolitho\$8 or expos\$4)) or ((liquid or fluid) near18 immersion near19 (system or apparatus or method))) and ((resist or photoresist or photosensitive or photo\$5cur\$5 or (radiation near9 sensitive)) same ((multi\$3 near9 resist) or (multiple near9 layer) or (double near9 \$5resist) or (dual\$5 near5 resist\$5 near5 layer) or bi\$4layer or protective or top\$6coat\$4 or upper\$8layer or hard\$5mask\$4 or over\$3coat\$4 or top\$4layer)) and (expos\$6 or illuminat\$4 or irradiat\$4) and ((acid or photo\$4acid or (therm\$5 near6 acid)) near15 (generat\$4 or liberat\$5)) and (BARC or (bottom near9 ARC) or (ARC near14 under\$3layer) or (bottom near13 anti\$5reflect\$6) or anti\$8reflect\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
18	72	((immersion near14 (lithograph\$8 or photolitho\$8 or expos\$4)) or ((liquid or fluid) near18 immersion near19 (system or apparatus or method))) and ((resist or photoresist or photosensitive or photo\$5cur\$5 or (radiation near9 sensitive)) same ((double near9 \$5resist) or (dual\$5 near5 resist\$5 near5 layer) or bi\$4layer or protective or top\$6coat\$4 or upper\$8layer or hard\$5mask\$4 or over\$3coat\$4 or top\$4layer)) and (expos\$6 or illuminat\$4 or irradiat\$4) and ((acid or photo\$4acid or (therm\$5 near6 acid)) near15 (generat\$4 or liberat\$5)) and (dissolut\$5 or dissolv\$4 or soluble or solubili\$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
19	38	S18 NOT S17	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
21	4	((immersion near14 (lithograph\$8 or photolitho\$8 or expos\$4)) or ((liquid or fluid) near18 immersion near19 (system or apparatus or method))) and (resist or photoresist or photosensitive or photo\$5cur\$5 or (radiation near9 sensitive)) and ((double near9 \$5resist) or (dual\$5 near5 resist\$5 near5 layer) or multilayer or bilayer or bi\$4layer or protective or top\$6coat\$4 or upper\$8layer or hard\$5mask\$4 or over\$3coat\$4 or top\$4layer) and (expos\$6 or illuminat\$4 or irradiat\$4) and ((acid or photo\$4acid or (therm\$5 near6 acid)) near15 (generat\$4 or liberat\$5)) and ((index near5 match\$4 near6 liquid) or IML) and (anti\$4reflect\$4 or ARC)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
22	4	((immersion near14 (lithograph\$8 or photolitho\$8 or expos\$4)) or ((liquid or fluid) near18 immersion near19 (system or apparatus or method))) and (resist or photoresist or photosensitive or photo\$5cur\$5 or (radiation near9 sensitive)) and ((double near9 \$5resist) or (dual\$5 near5 resist\$5 near5 layer) or multilayer or bilayer or bi\$4layer or protective or top\$6coat\$4 or upper\$8layer or hard\$5mask\$4 or over\$3coat\$4 or top\$4layer) and (expos\$6 or illuminat\$4 or irradiat\$4) and ((acid or photo\$4acid or (therm\$5 near6 acid)) near15 (generat\$4 or liberat\$5)) and ((index near5 match\$4 near6 liquid) or IML)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
23	3	((immersion near14 (lithograph\$8 or photolitho\$8 or expos\$4)) or ((liquid or fluid) near18 immersion near19 (system or apparatus or method))) and (resist or photoresist or photosensitive or photo\$5cur\$5 or (radiation near9 sensitive)) and ((double near9 \$5resist) or (dual\$5 near5 resist\$5 near5 layer) or multilayer or bilayer or bi\$4layer or protective or top\$6coat\$4 or upper\$8layer or hard\$5mask\$4 or over\$3coat\$4 or top\$4layer) and (expos\$6 or illuminat\$4 or irradiat\$4) and ((acid or photo\$4acid or (therm\$5 near6 acid)) near15 (generat\$4 or liberat\$5)) and ((prevent\$5 or avoid\$4) same diffus\$3 same photoresist same (liquid or IML or fluid or (immersion near9 liquid)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
24	4	(immersion near14 (lithograph\$8 or photolitho\$8 or expos\$4)) and (resist or photoresist or photosensitive or photo\$5cur\$5 or (radiation near9 sensitive)) and ((double near9 \$5resist) or (dual\$5 near5 resist\$5 near5 layer) or multilayer or bilayer or bi\$4layer or protective or top\$6coat\$4 or upper\$8layer or hard\$5mask\$4 or over\$3coat\$4 or top\$4layer) and (expos\$6 or illuminat\$4 or irradiat\$4) and ((acid or photo\$4acid or (therm\$5 near6 acid)) near15 (generat\$4 or liberat\$5)) and ((prevent\$5 or avoid\$4) same diffus\$3 same photoresist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
25	4	(immersion near14 (lithograph\$8 or photolitho\$8 or expos\$4)) and (resist or photoresist or photosensitive or photo\$5cur\$5 or (radiation near9 sensitive)) and ((double near9 \$5resist) or (dual\$5 near5 resist\$5 near5 layer) or multilayer or bilayer or bi\$4layer or protective or top\$6coat\$4 or upper\$8layer or hard\$5mask\$4 or over\$3coat\$4 or top\$4layer) and (expos\$6 or illuminat\$4 or irradiat\$4) and (((acid or photo\$4acid or (therm\$5 near6 acid)) near15 (generat\$4 or liberat\$5)) or (chemical\$4 near amplification near9 resist) or CAR) and ((prevent\$5 or avoid\$4) same diffus\$3 same photoresist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB